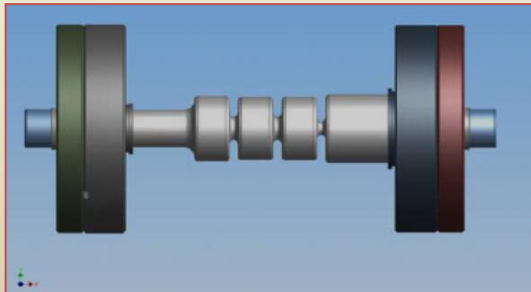
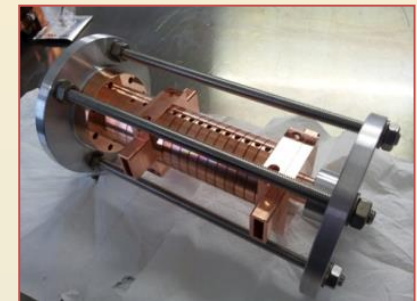
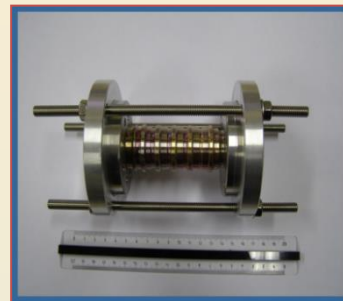
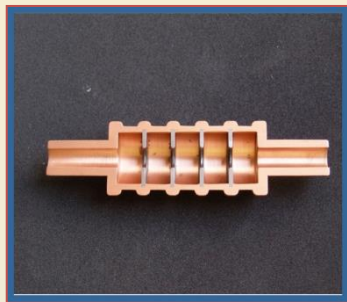


# Achievements and activities on X-band accelerator structures at LNF

presented by **Bruno Spataro**  
on behalf of NORCIA experiment **INFN-LNF**



## Contributors

**This work is made possible by the efforts :**

**NORCIA Group, INFN - LNF**

**A. Marcelli, INFN-LNF and NSRL/USTC (P.R. China)**

**V. Rigato, INFN - LNL**

**V. Dolgashev, S. Tantawi , A.D. Yeremian, SLAC**

**Y. Yigashi, KEK**

**L. Palumbo, University of Roma 1**

**J. Rosenzweig, UCLA**

# SUMMARY

- **Status of the technological activity**
- **Advancements on electroforming**
- **Resistivity measurements of Mo films**
- **Morphological characterization of surfaces after RF higher power tests**
- **How to achieve a higher peak field on the cathode working with a 11.424 GHz hybrid photoinjector?**

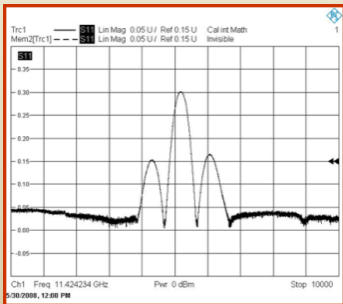
# NOvel Researches Challenges In Accelerators

[http://www.Inf.infn.it/gr5/website\\_norcia/home.html](http://www.Inf.infn.it/gr5/website_norcia/home.html)



Molybdenum brazed

NIM-A-657 (2011) 114-121

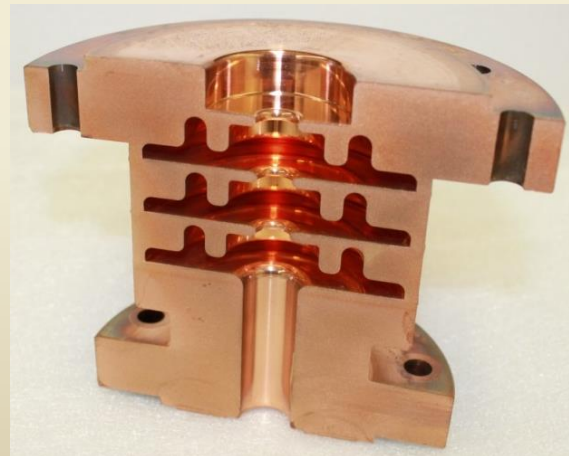


Pi mode field profile



Cu brazed

Applied Physics Letters 97, 171501



Triple-choke

Cu electron-beam welded  
(studies in progress)



Cu electroplated  
(hard copper)

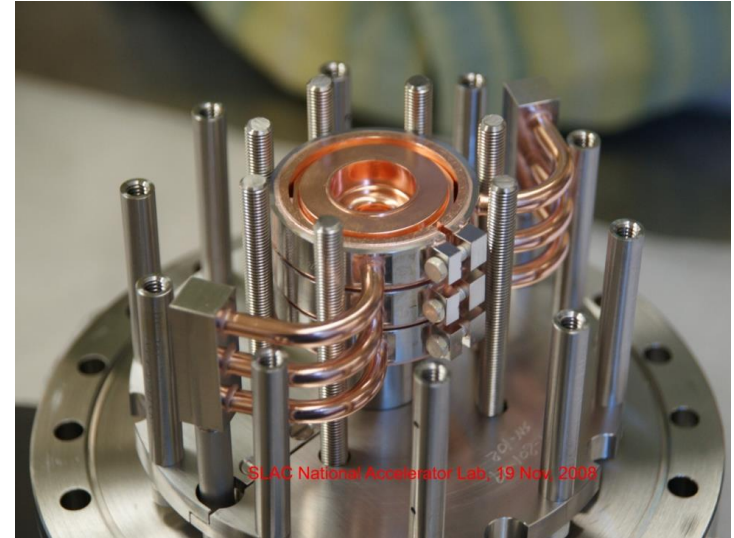
NIM-A-657 (2011) 88-93

(A.D. Yeremian, V.A. Dolgashev,  
S.G. Tantawi, SLAC)

# Development of Hard Copper Structures

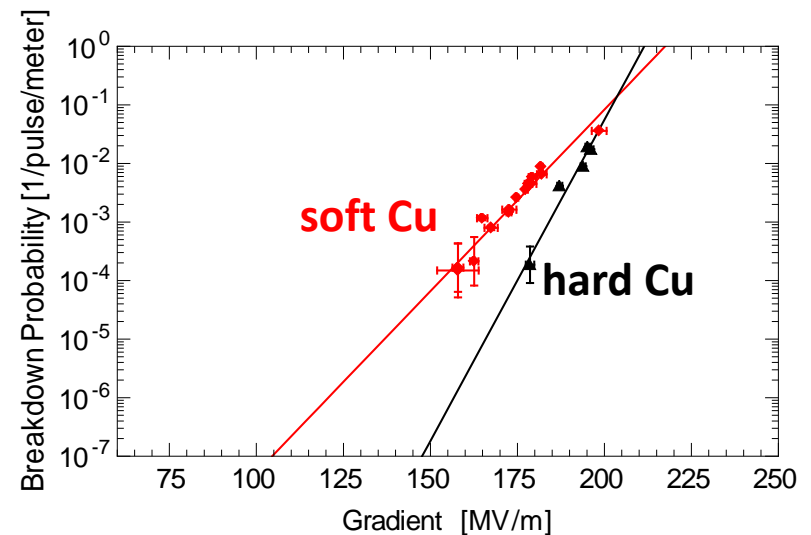
(V.A. Dolgashev, S. Tantawi et al. SLAC)

- We had to develop an apparatus for testing accelerator structure without brazing
- The results show a great improvement of possible gradients at very low breakdown rates
- It is now possible to talk about reliable gradient higher than 150 MV/m

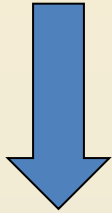


1C-SW-A2.75-T2.0  
copper structures,  
200ns flat pulse

**Moreover, additional tests at SLAC on hard 'initial CuAg 'alloy' are better !!**



# Sintered molybdenum (bulk) issue



**long time for  
machining  
the cavity**



**~ 250 nm roughness  
using 'tungsten  
carbide' tools**



**It is not easy to braze.  
It is likely to have a gas  
contamination and an uneven  
loading stress in the braze  
region (joints are not  
completely filled with alloy ).**

**New technologies are required for multi-TeV linear colliders, x-ray FELs, etc.**

**The research project is devoted to the R&D of key components for existing accelerators and for the next generation of accelerators**



**Approach:**

**New materials and manufacturing techniques including single and multi-layer surfaces with precision-controlled properties**

# X-band device realisation issues

## Guidelines:

How to improve the high power performance (e.g. discharge rate) ?

- using materials with higher fusion temperature;  R&D on materials
- avoiding the device heating at high temperature as done in **conventional brazing**  R&D on fabrication techniques

R&D on material



• Sintered Molybdenum (Bulk)

R&D on fabrication techniques



• Electroforming

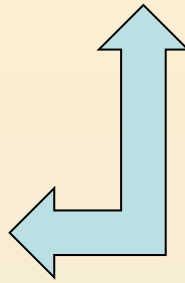
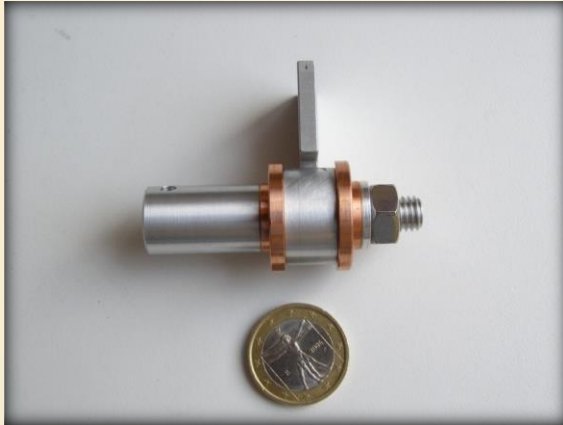
• Soft Bonding

• Molybdenum sputtering on Copper

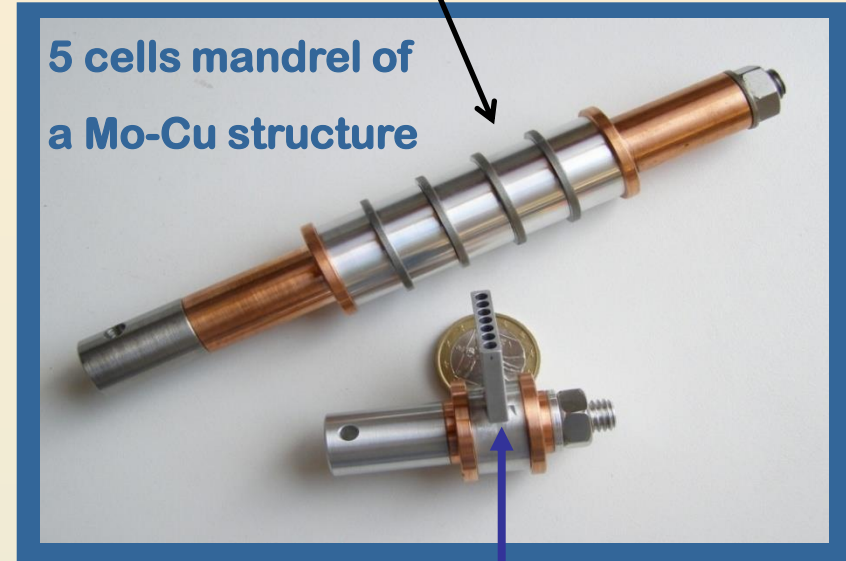
• EBW (Electron Beam Welding)



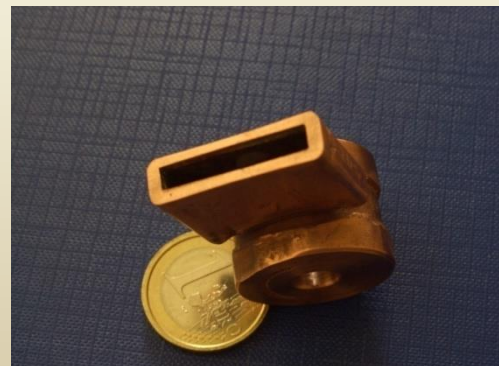
**Aluminium mandrel of the RF coupler and cell ready for the electroforming**



**Mo discs are already machined to be the iris of the electroformed cell**



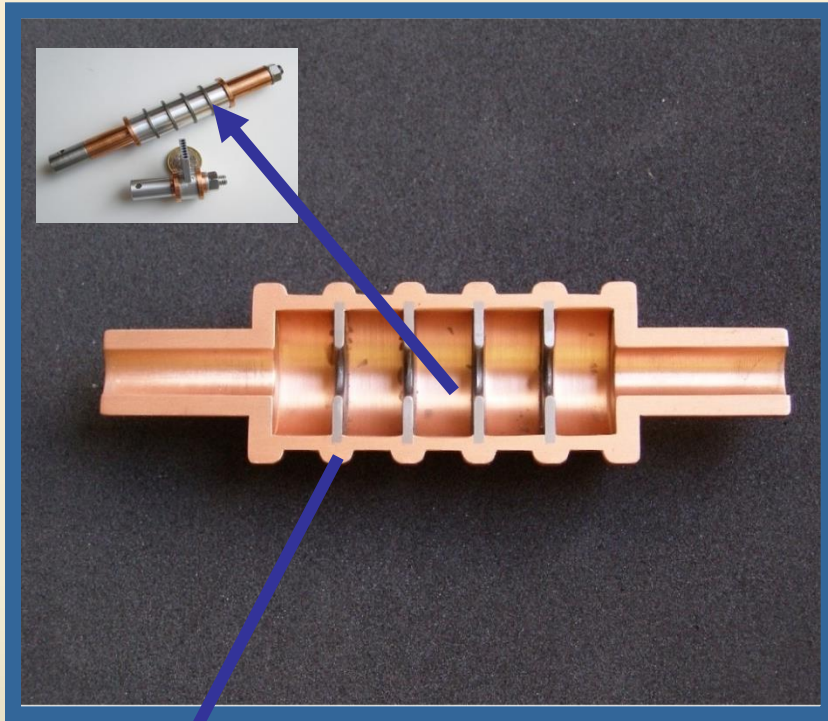
**Electroformed RF coupler and cell**



**Another view of the coupler mandrel is shown**

..... *Electroforming R&D and Test*

RF cells after removing the aluminium core with alkaline solution (sodium hydroxide NaOH). Cross section of a Mo-Cu electroformed structure.

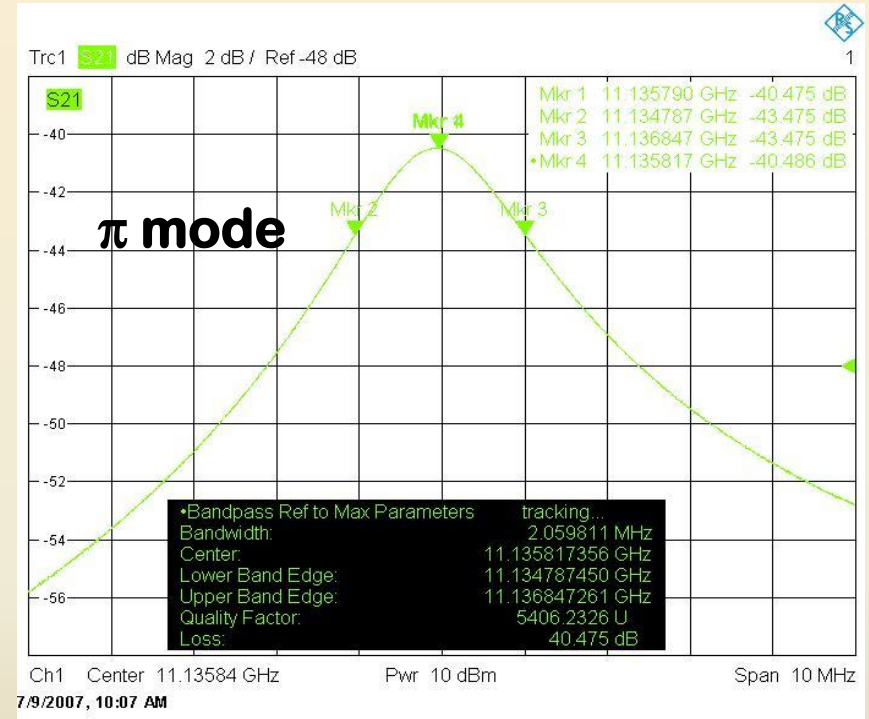


The Mo discs improve the mechanical properties with the external ribs .

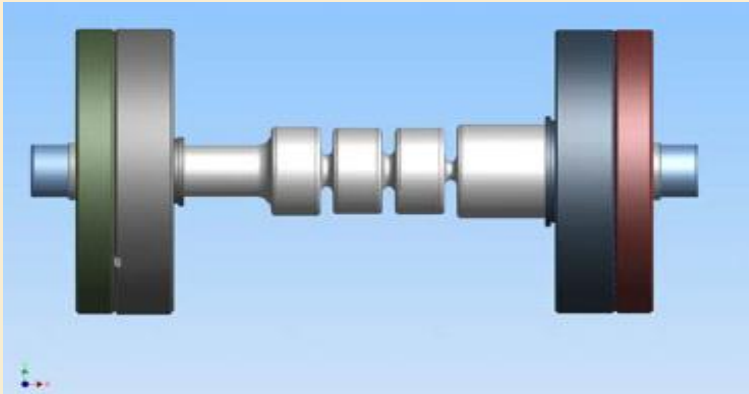
Next step: to improve the quality of the Cu surface altered by the alkaline solution depositing silver or gold on the core or using other methods ....  
In addition to improve the Mo surface roughness (~ 250 nm !!)

Fundamental mode response of Cu-Mo electroformed structure

$$Q_0 = 5406$$



# NORCIA's prototypes made by COMEB and MLT Companies



**Prototype mandrel  
for the electroforming**



**3  $\mu\text{m}$  thick Au coating**



**Fitting test between mandrel  
and CF flanges**



**Au coated structure with  
a 4 mm thick Nickel coating**

# 11.424 GHz cross section of the electroformed cavity (Au-Ni)

Iris thickness 2 mm

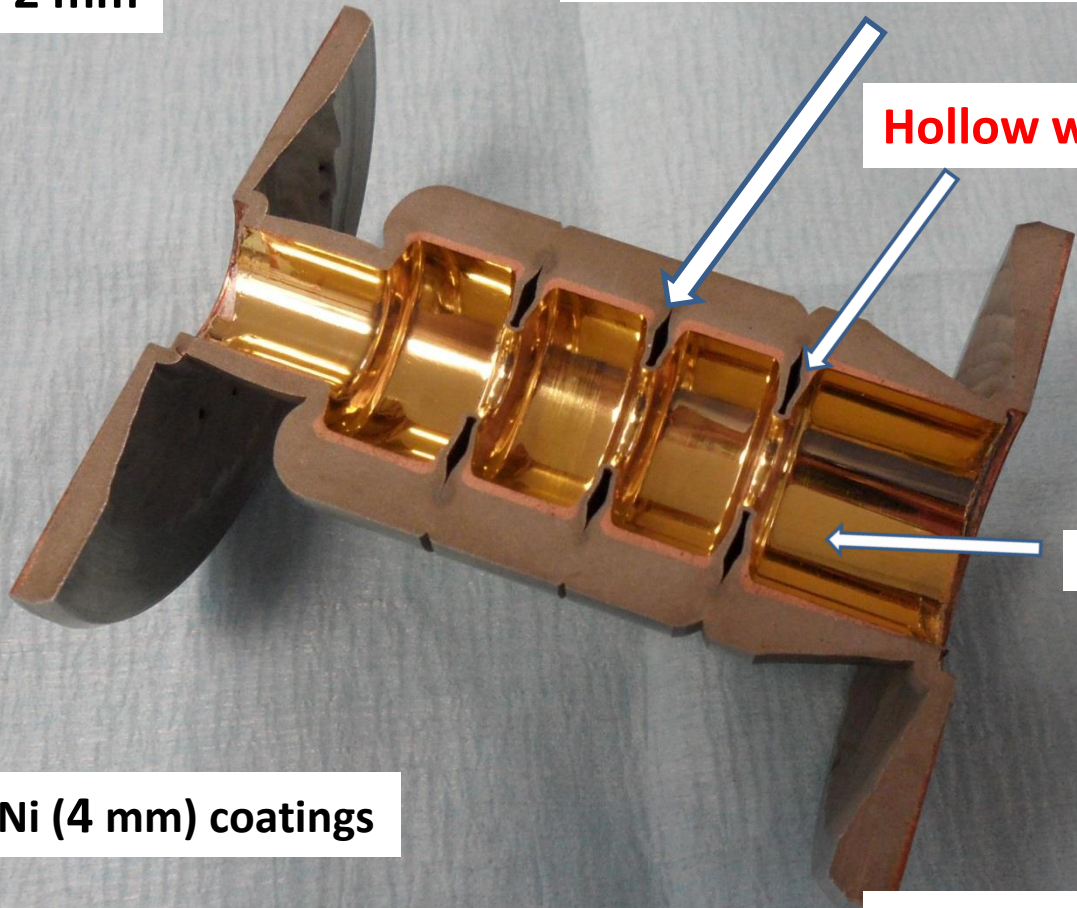
Hollow of the iris's cooling

Hollow wall thickness 0.5 mm

70 nm roughness

Au (3  $\mu\text{m}$ ) and Ni (4 mm) coatings

(COMEB and MLT Companies)

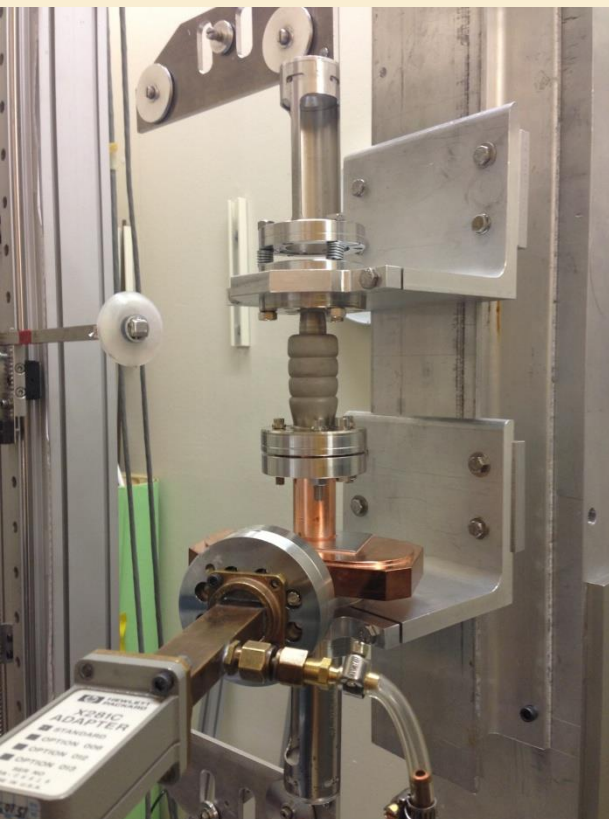


# Iris cooling (COMEB & MLT Company)

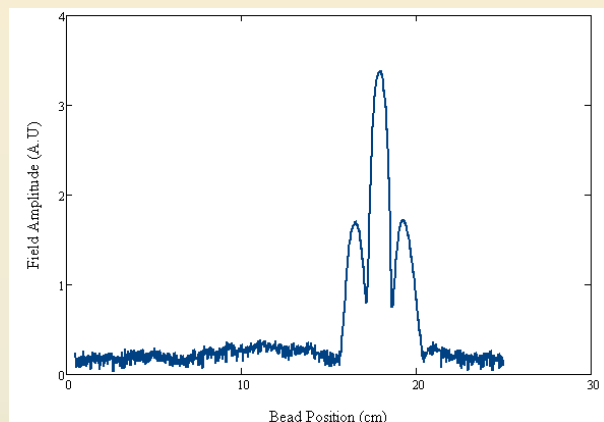


# Summary of RF QC for 1C-SW-A3.75-T2.6-Electroformed-Au-Frascati-#1

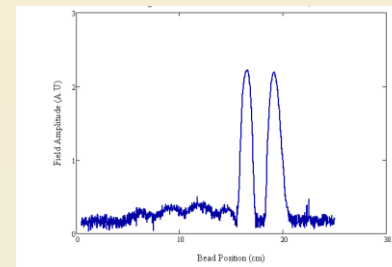
Mode	Freq(GHz)	Qzero	QI	Qext	Beta
Pi	11.4154	5786	3486	8774	.659
Pi/2	11.3214	6621	1847	2561	2.58
Zero	11.2692	7090	1949	2688	2.64



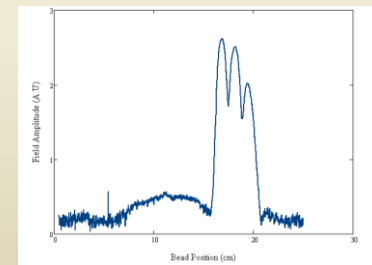
Bead-pull setup



On-axis field amplitude,  
Pi- mode, 11.4154 GHz

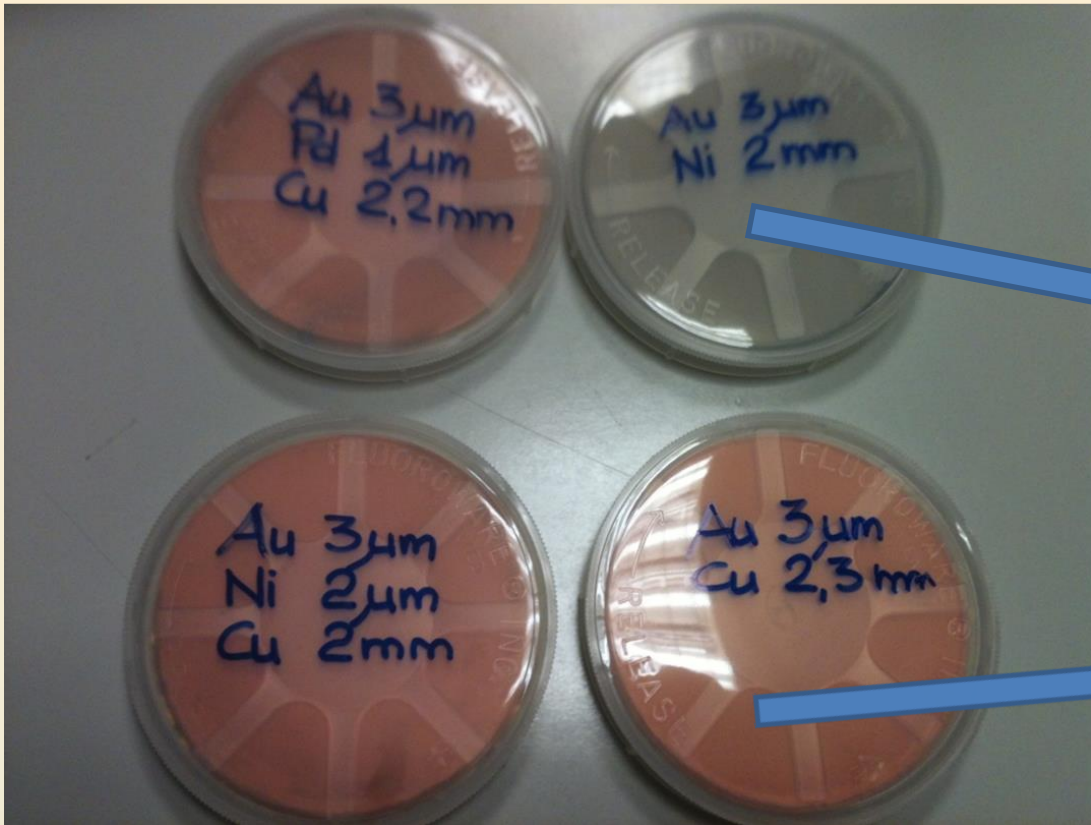


On-axis fields of Pi/2  
Mode, 11.32825GHz



On-axis fields of 0  
Mode, 11.2692 GHz

# Flat samples for the resistivity measurements



These flat samples have resistivity  $\sim 1.2$  worse than Cu (SLAC- V. Dolgashev et al.)

(COMEB & MLT Companies)

The first flat samples have been prepared using combination of :

PVD Au (200nm)+ Galvanic Gold (4 micron)

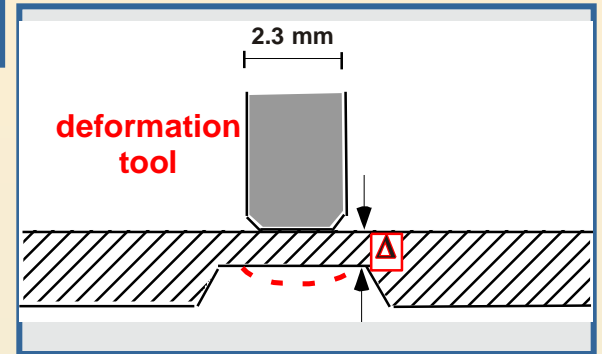
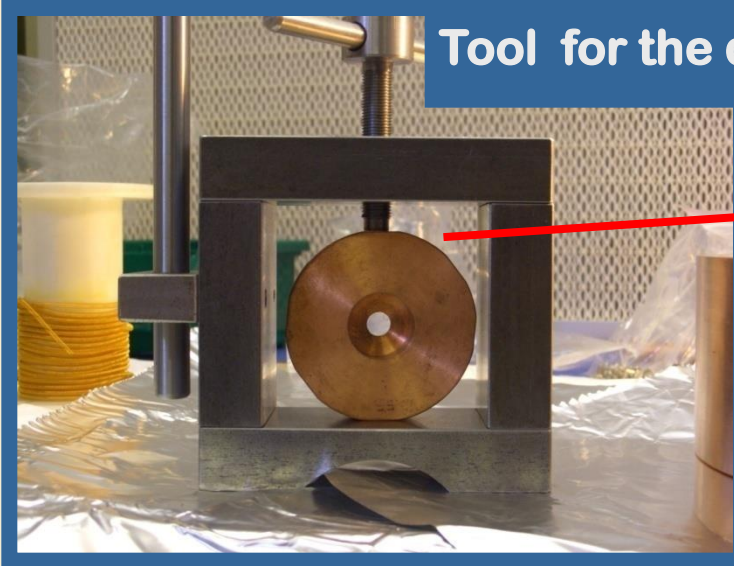
Flash adhesion layer PVD or galvanic (Pd, Ni)

typically 0.5 micron;

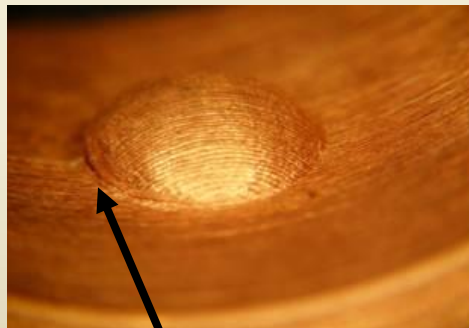
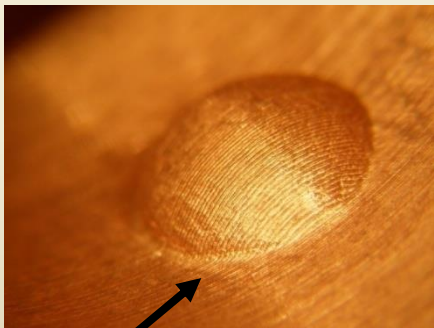
E-formed Ni or Cu

# Tuning with the wall deformation

Tool for the deformation test

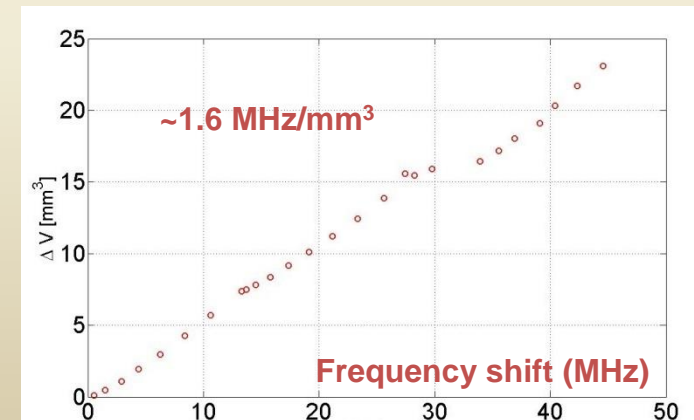


CU	MO
$\Delta = 0.9 \text{ mm}$	$\Delta = 0.8 \text{ mm}$
deform $\leq 0.6 \text{ mm}$	deform $\leq 0.3 \text{ mm}$



Detail of the maximum deformation obtained inside the cell [Master thesis of M. Ronzoni – University La Sapienza – Rome]

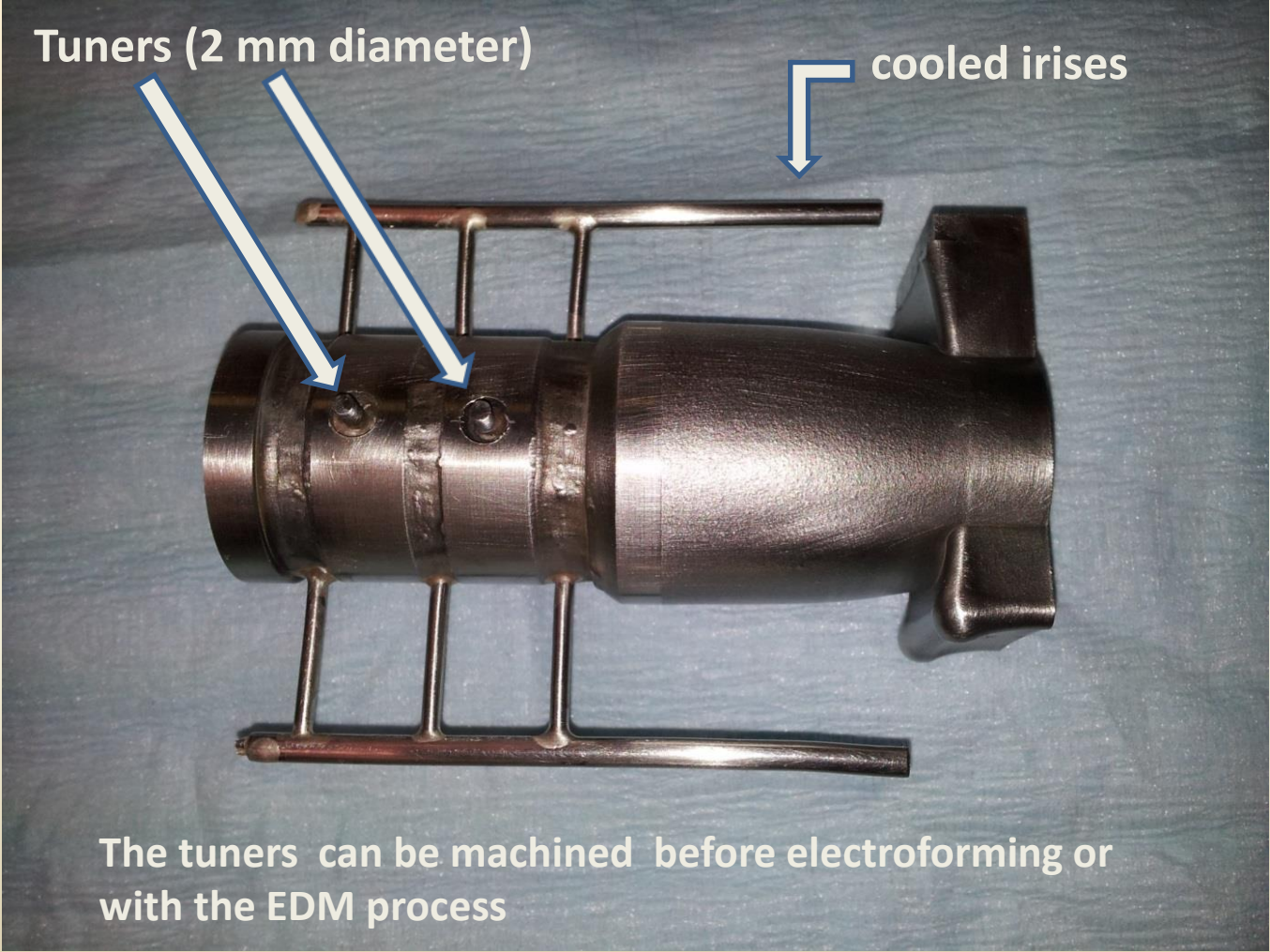
Breaking limit





# X band Galaxie gun prototype (J. Rosenzweig - UCLA) with cooled irises

## Manufactured with the electroforming process



**(COMEB & MLT Companies)**

# First conclusions and Open problems (on electroforming activities)

We built two structures: Au-Ni and Au-Cu. The field profile and frequency are satisfactory for both sections.

Flat samples resistivity is  $\sim 1.2$  worse than Cu (SLAC - V. Dolgashev et al.)

Structures resistivity is  $\sim 2.5-3$  worse than Cu (SLAC - V. Dolgashev et al.). The deposition with the galvanic process occurring at grazing angles affects the film's compactness (due mainly to the porosity inside the film)

The sodium hydroxide (NaOH) removes the Al mandrel but does not affect the Au deposited film. The latter is required to stop the erosion of the mandrel.

The cooling of the iris with a 2 mm thickness was successful !

# Possible alternative approach to the galvanic process in order to improve the film's conductivity

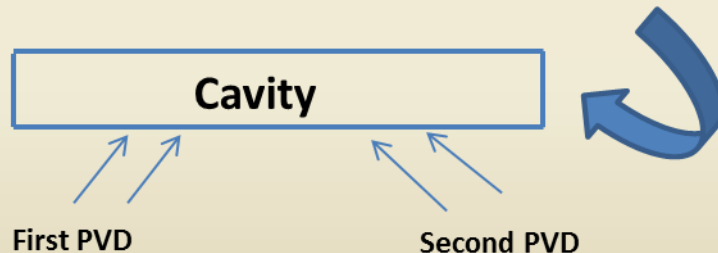
In general coatings with PVD processes resulted with a much better purity compared to galvanic ones

The PVD gold has highest purity with respect to the galvanic gold.

We propose to perform two film deposition steps of PVD gold with an angle, while the mandrel is turning (continuous rotation).

This layout may deposit at an angle of  $\pm 30$  deg growing a layer of Au more homogeneous and with a lower porosities.

(tests are planned on dedicated prototypes)



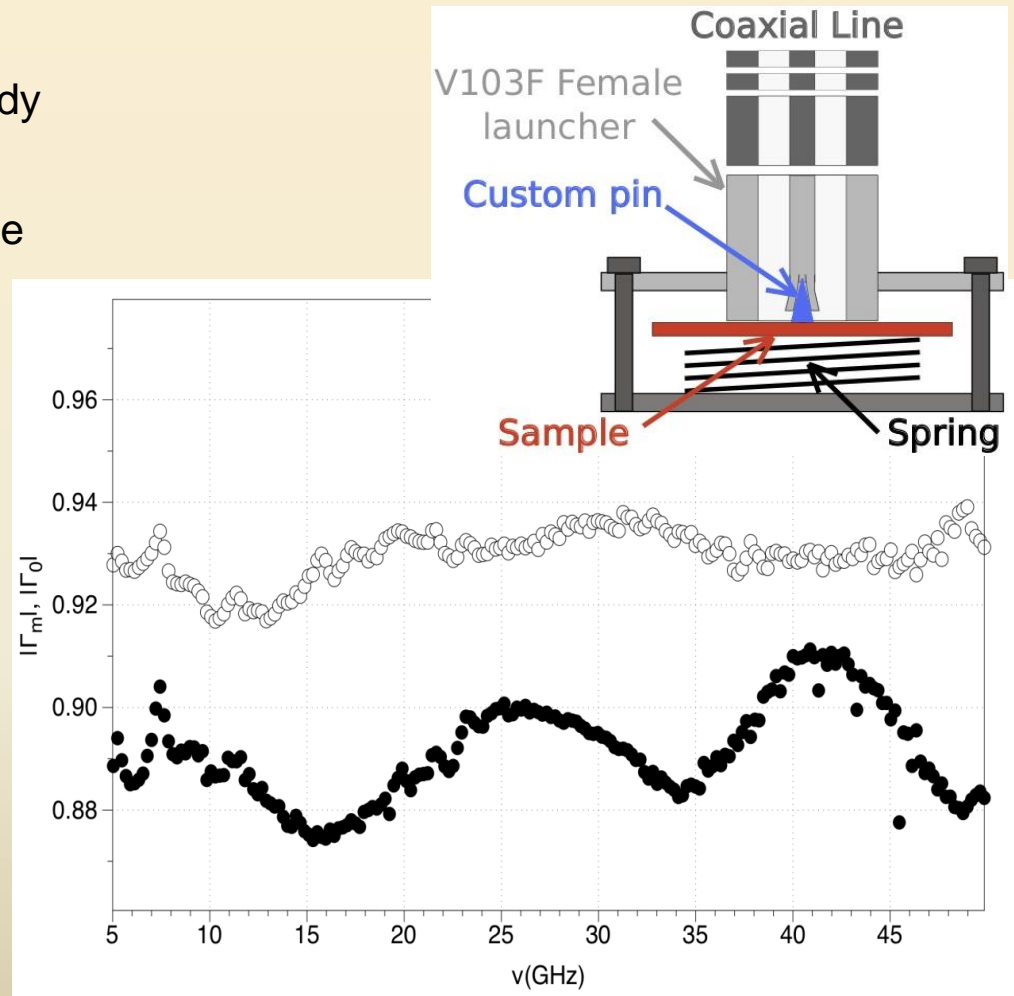
Film deposition onto trenches region (as the iris) with an aspect ratio 3-4 by using the IONIZED MAGNETRON SPUTTERING may improve film structure and density (tests are planned on dedicated prototypes)

# Resistivity measurements of the Mo film deposited **on a insulating layer**

- Reflection coefficient of a line terminated onto the film under study (full symbols)
- Subtract the contribution due to the uncalibrated line segment (open symbols)
- Obtain resistivity:

$$\frac{\rho}{d} \simeq Z_0 \frac{1 + \Gamma_0}{1 - \Gamma_0}$$

Where  $Z_0$  is the impedance of the line.



S. Ganchev, N. Qaddoumi, S. Bakhtiari, R. Zoughi, IEEE Trans. Instr. Meas 44, 1023 (1995)

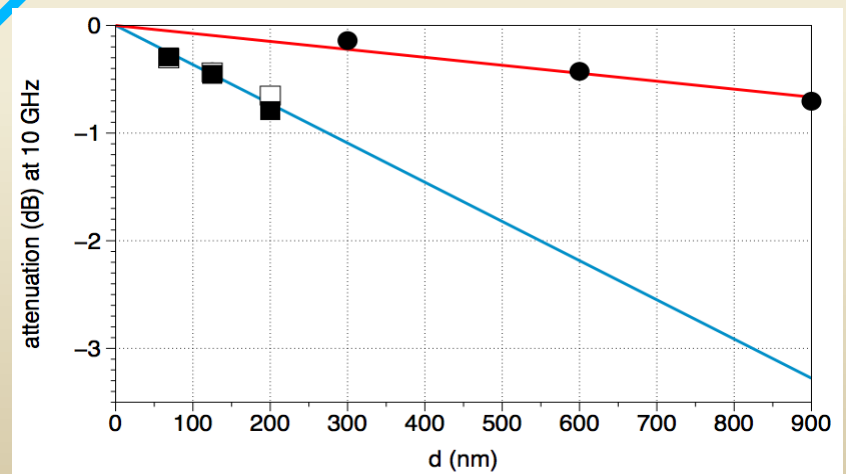
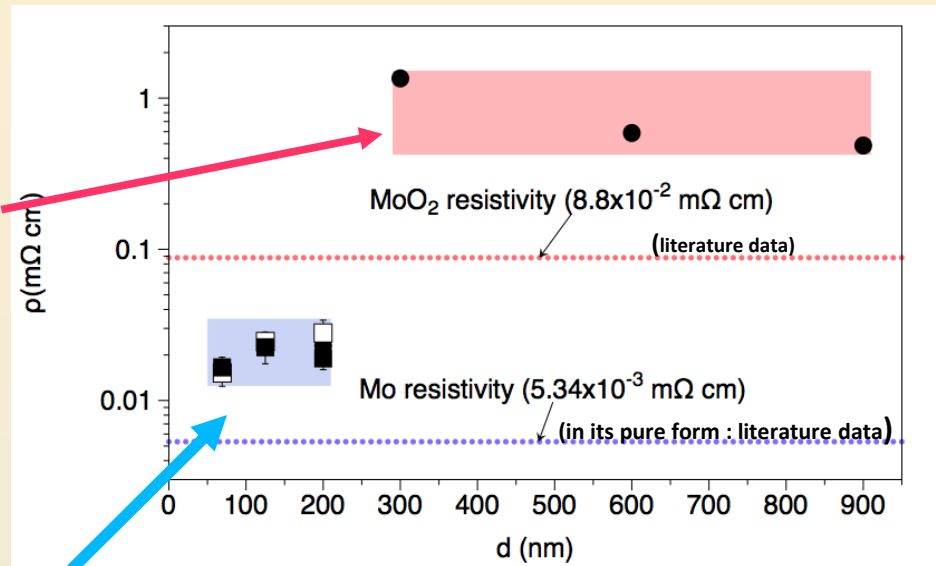
N. Tosoratti, R. Fastampa, M. Giura, V. Lenzi, S. Sarti and E. Silva, Int. J. Mod. Phys. B 14, 2926 (2000)

# Resistivity measurements of Mo films

XAS (X-ray Absorption Spectroscopy) and X-ray Diffraction (XRD) experiments are in progress at Diamond Light Source (UK) in order to characterize the chemical status of Mo film

Additional measurements carried out at Catania are in agreement with our results

Substrate	O <sub>2</sub> pressure	thickness (nm)	$\rho$ (m $\Omega$ cm)
Glass	10 <sup>-2</sup>	300	1.35
Glass	10 <sup>-2</sup>	600	0.59
Glass	10 <sup>-2</sup>	900	0.49
Glass	1.5 × 10 <sup>-2</sup>	70	1.6 × 10 <sup>-2</sup>
Glass	1.5 × 10 <sup>-2</sup>	125	2.5 × 10 <sup>-2</sup>
Glass	1.5 × 10 <sup>-2</sup>	200	2.3 × 10 <sup>-2</sup>
Glass	10 <sup>-3</sup>	70	1.5 × 10 <sup>-2</sup>
Glass	10 <sup>-3</sup>	125	2.5 × 10 <sup>-2</sup>
Glass	10 <sup>-3</sup>	200	2.8 × 10 <sup>-2</sup>
Al <sub>2</sub> O <sub>3</sub>	10 <sup>-3</sup>	70	1.7 × 10 <sup>-2</sup>
Al <sub>2</sub> O <sub>3</sub>	10 <sup>-3</sup>	125	2.2 × 10 <sup>-2</sup>
Al <sub>2</sub> O <sub>3</sub>	10 <sup>-3</sup>	200	1.9 × 10 <sup>-2</sup>

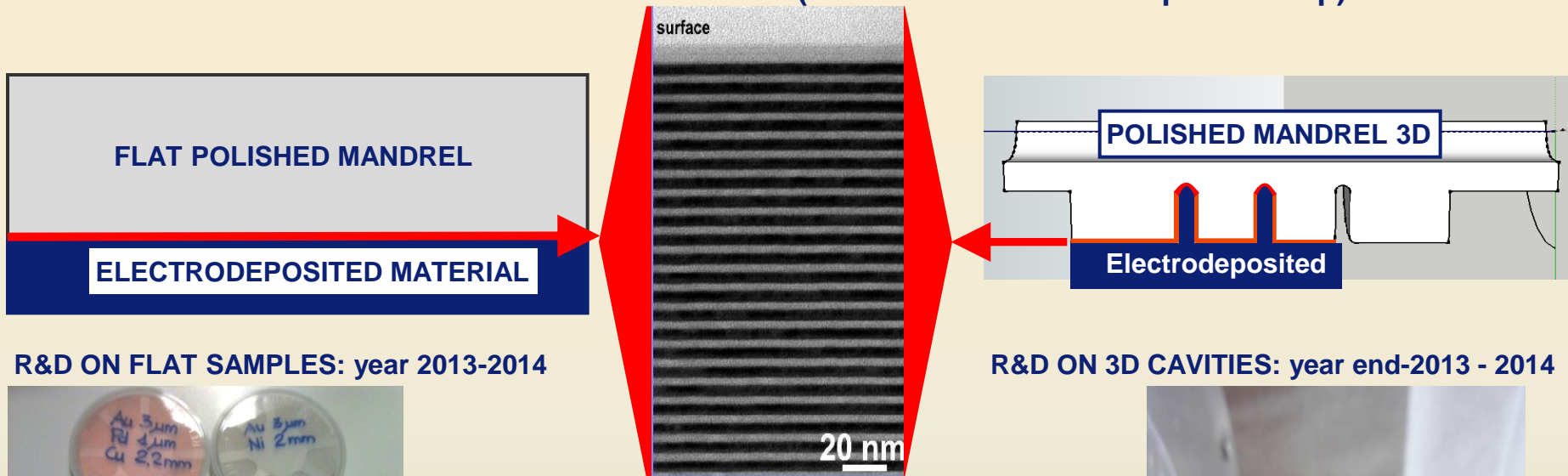


Chinese Physics C 36, (2012)

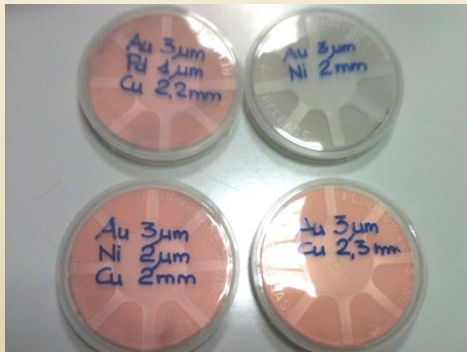
Chinese Physics C 37, (2013)

# TECHNOLOGY ADVANCES OUTLINE

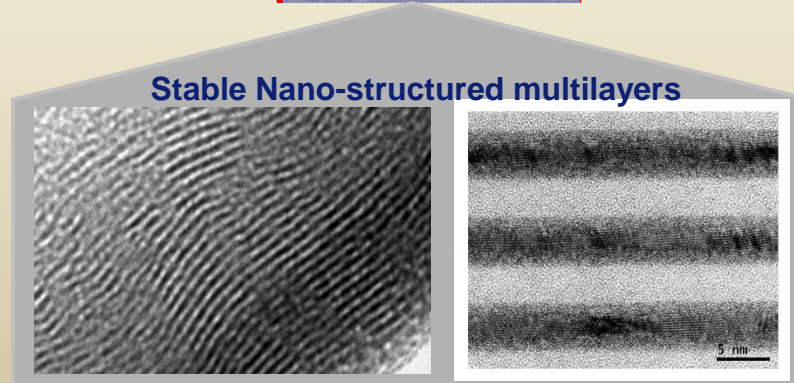
- STEP 1 = MANDREL PRODUCTION (INFN Design, outside manufacture e.g. diamond turning, super-polishing)
- STEP 2 = DEPOSITION OF NANOSTRUCTURED MULTILAYER (LNL)
- STEP 3 = ELECTRO-DEPOSITION OF THICK BODY STRUCTURE (external partnership)
- STEP 4 = MANDREL REMOVAL / DISSOLUTION (both INFN and external partnership)



R&D ON FLAT SAMPLES: year 2013-2014



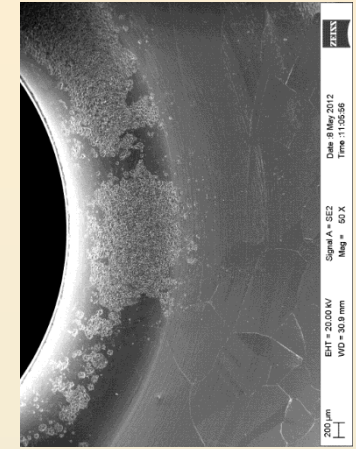
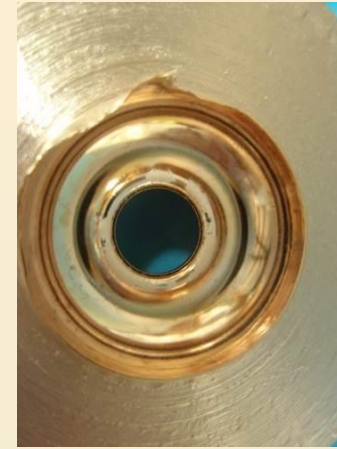
R&D ON 3D CAVITIES: year end-2013 - 2014



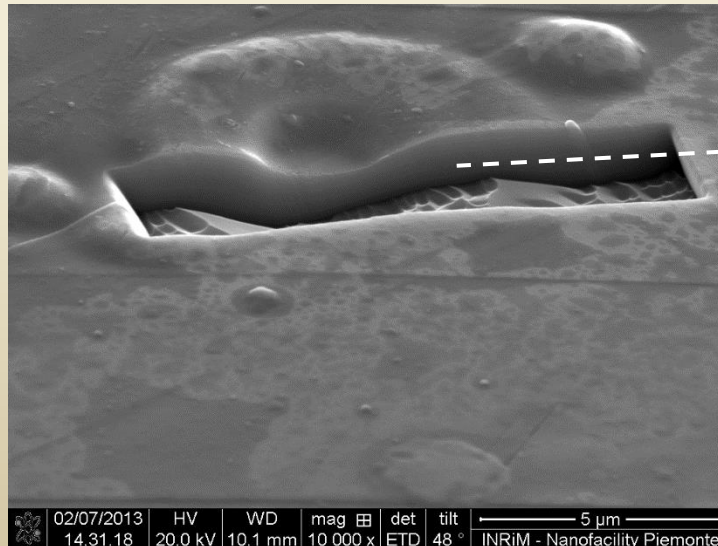
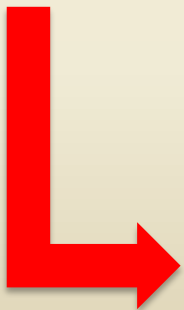
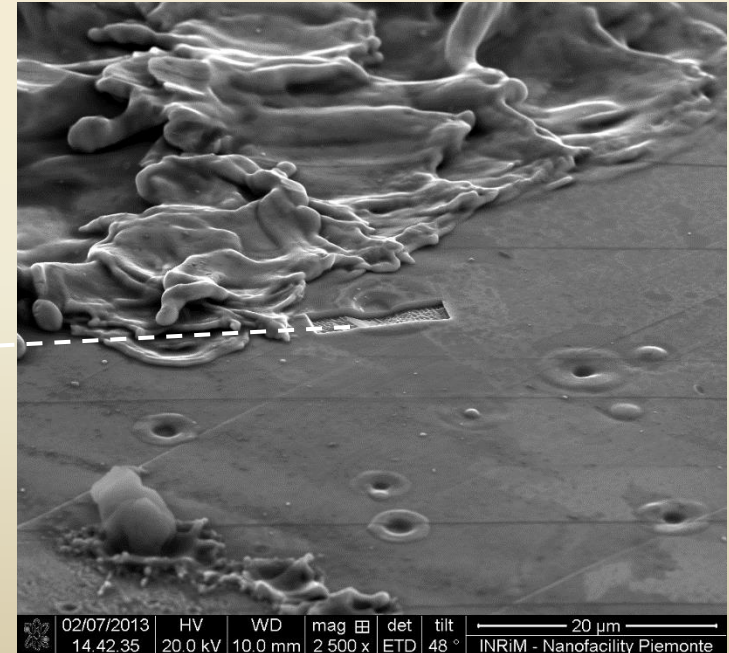
Stable Nano-structured multilayers

# Cross sections preparation and defects analysis ( preliminary morphological characterization)

- 1C-SW-A3.75-2.2-Cu-SLAC-1 (Elliptical design) 2013 – provided by **SLAC** (courtesy **V. Dolgashev**) after high power microwave tests
  - Sample for cross section analysis with electron microscopy
  - Electron microscopy (SEM-FEG + FIB)



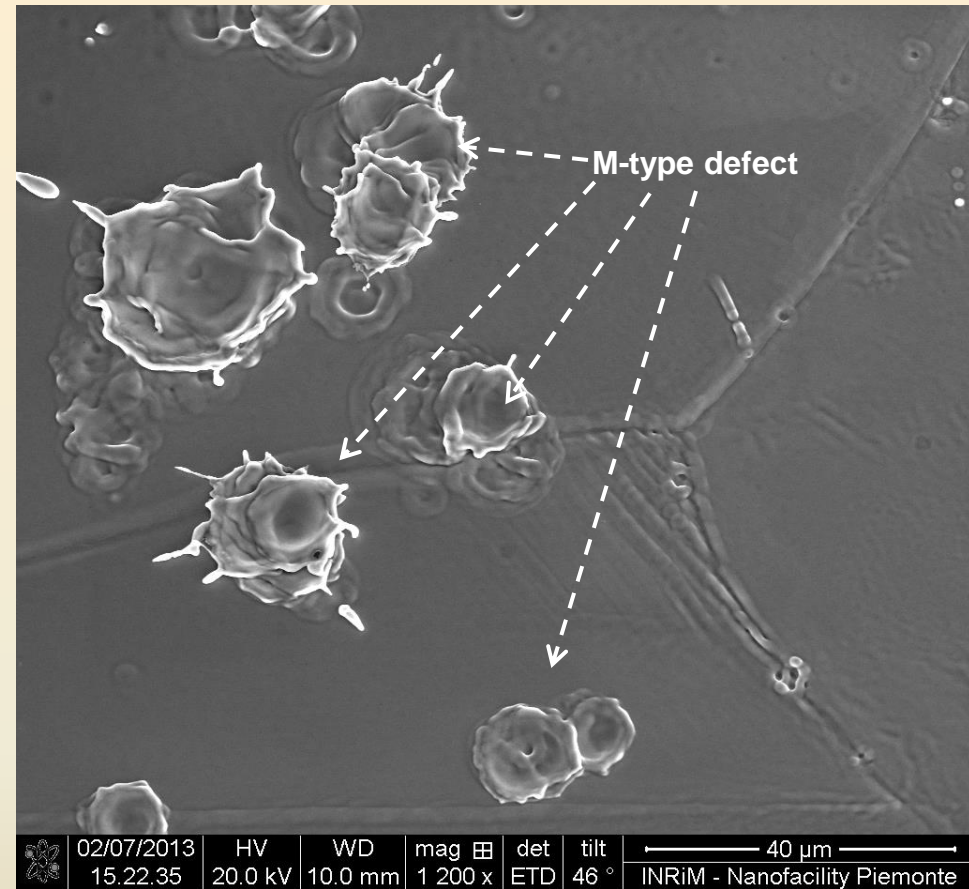
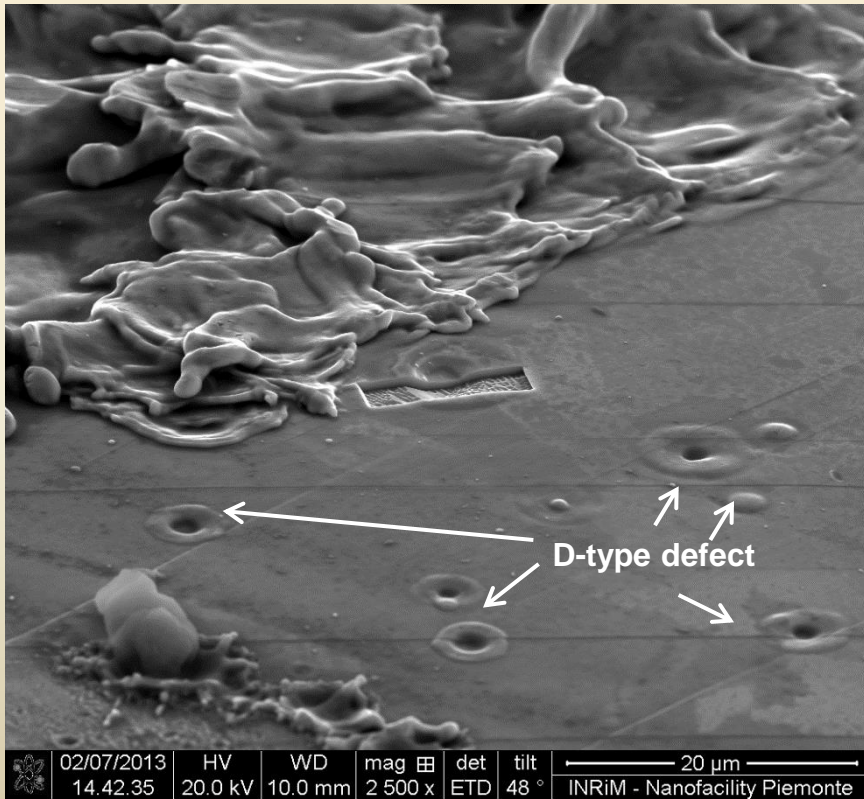
**FIB cross section of an isolated defect at the edge of a damaged region (~800 um from the edge of the iris)**



# ISOLATED SURFACE DEFECTS (II)

(preliminary morphological characterization)

- Isolated defects are interesting to understand the degradation phenomenon for X-band cavities



D-type and M-type defects seem to be of the same origin, but the process of melting/explosion is limited in D-type by the power delivered locally.

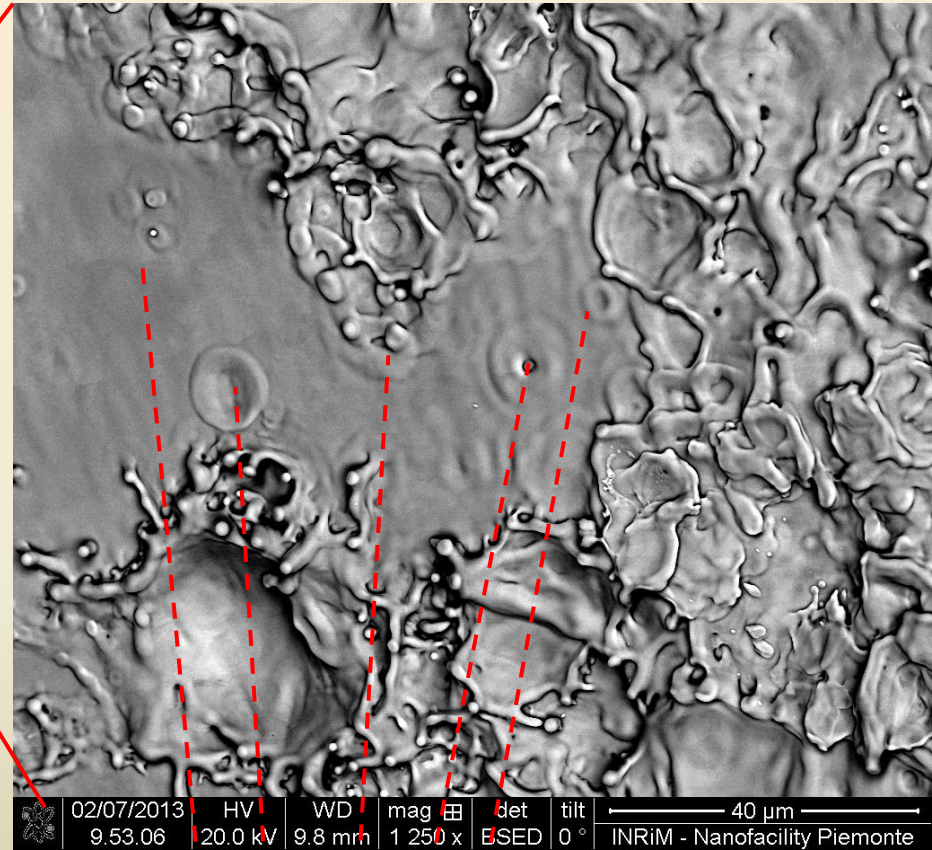
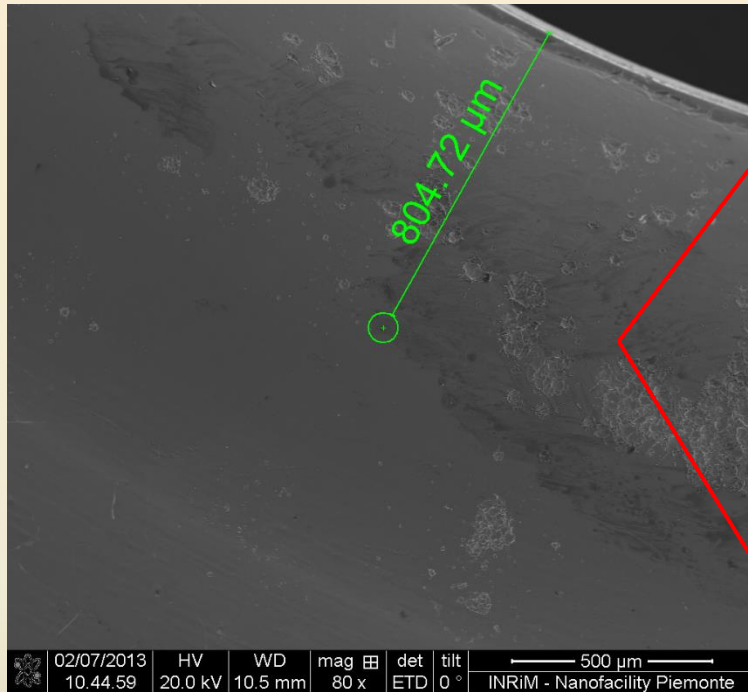
D stands for «Doughnut»

M stands for «Melted»



# SURFACE at micrometer scale (sample provided by V. Dolgashev)

- Extended zones evidence melting of copper in the region up to about 800um distance from iris tip.
- Melting of copper is almost continuous near iris tip
- **Isolated defects are seen at border-line region at distances about 800um from iris tip**



Examples of  
Isolated defects

- Analysis of isolated defects is important to understand deterioration phenomena, it is assumed that they may be «precursor» of melted spots (i.e., the early stages of a process of incomplete localized melting)

# Why 3D X-ray Imaging of IRIS?

Damaged “patches”, typical for single-cell-standing-wave-structure tests

We are interested in crystal defects and voids 0.....100 micron under these patches

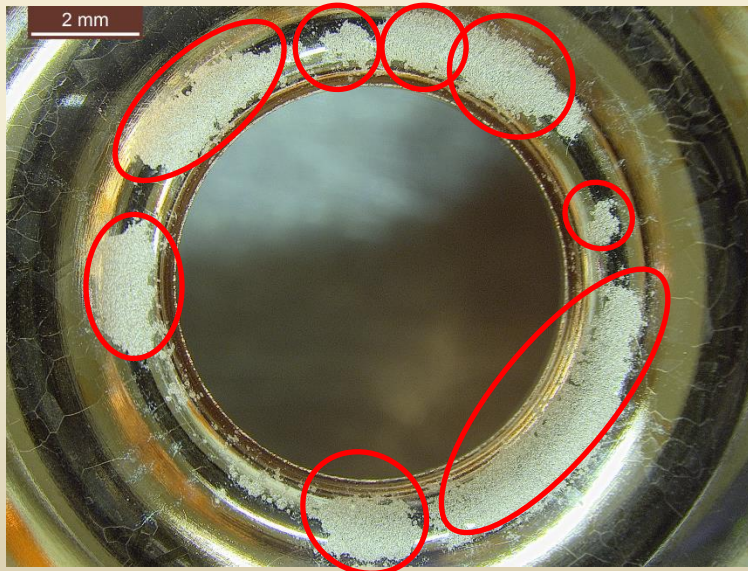
See GE x-ray computed –tomography imaging machines for industrial applications:

<http://www.ge-mcs.com/en/radiography-x-ray/ct-computed-tomography/nanotom-s.html>

We can carry out test on an entire iris



← Iris sectioned from the original part

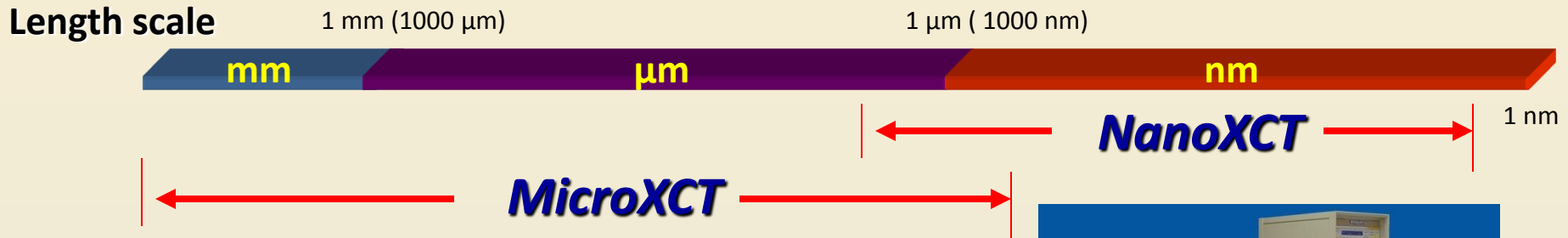


1C-SW-A3.75-T2.2-Cu-SLAC-1

# MicroXCT vs. NanoXCT ?

The device has an imaging resolution with length scale from several mm to tens of nm

- Unique Power
- Non-destructive
- High Resolution



# Advantages of X-ray Imaging

- *Short wavelength for high resolution*
- *Rich image contrast mechanism: absorption, chemical state, phase, diffraction, polarization*
- *Element specific: absorption edges and characteristic fluorescence*
- *High penetration for nondestructive imaging*
- *No charging effect on image resolution*



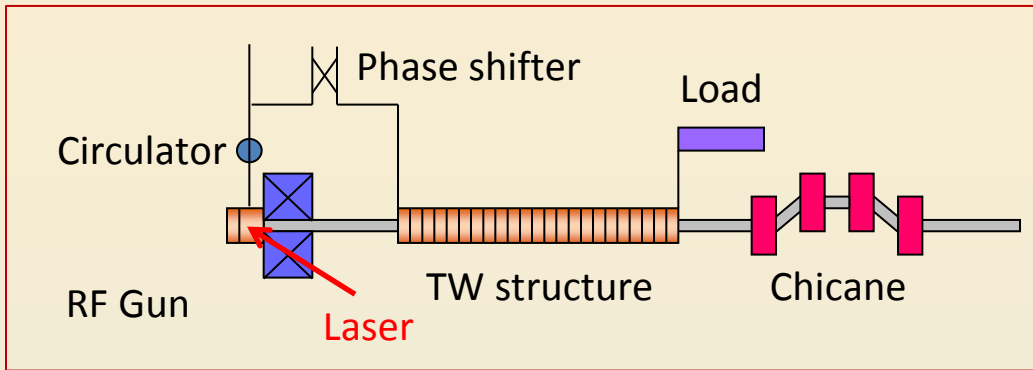


- For the requirement of basic research and industrial material studies, x-ray imaging facility in China will provide:
  - ✓ Brilliance of  $10^{21}$ - $10^{22}$ ph/s/mm<sup>2</sup> mrad<sup>2</sup>/0.1% BW
  - ✓ Focus spot down to 1mm (for coherent diffraction) or 10 nm (for nano-probe)
  - ✓ Photon energy up to 300 keV

# Conventional photoinjector vs. Hybrid photoinjector: RF properties

The photoinjector design employs a combination of two accelerating structures: a standing wave gun and an accelerating linac

## Conventional photoinjector

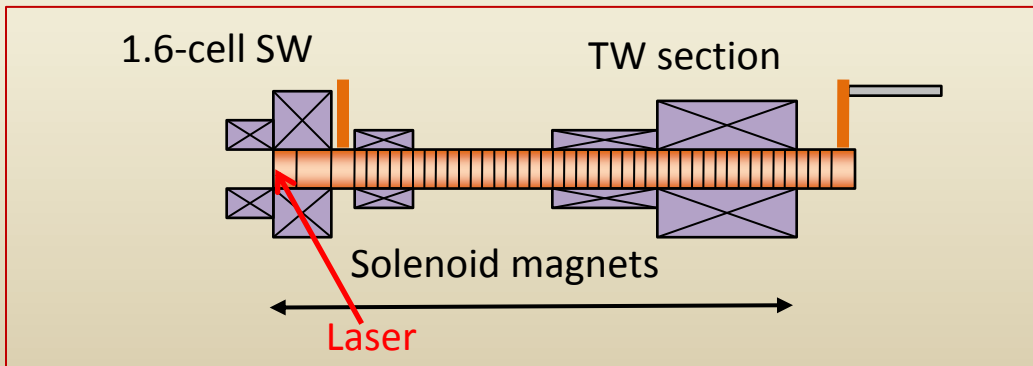


- The SW and TW structures are fed independently
- The SW structure reflects nearly all of the input power at the beginning of the RF fill process



**circulators** are necessary in order to protect the RF power source

## Hybrid photoinjector



- The SW RF gun section is coupled on-axis to the TW section through a coupling cell that serves as feeding system to both SW/TW.



This enables to build a RF gun at higher frequency where no adequate high power circulators yet exist

# X-band hybrid photoinjector: first step

- S-Band hybrid + Scaling Laws

## S-Band Main parameters:

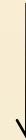
- Frequency : 2.856GHz
- Total length : 300cm
- Peak field in SW : 60MV/m
- Charge : 1n

DIMENSIONS  $\propto 1/f$   
FIELD  $\propto f$   
CHARGE  $\propto 1/f$

## X-Band Main parameters:

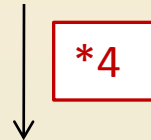
- Frequency : 11.424GHz
- Total length : 75cm
- Peak field in SW : 240MV/m  $\rightarrow$  200MV/m
- Charge : 250pC

While scaling the design from S-Band to X-Band is conceptually simple



**Practical limits** require some changes in both RF and magnetostatic designs:

Scaling factor  
2.856GHz



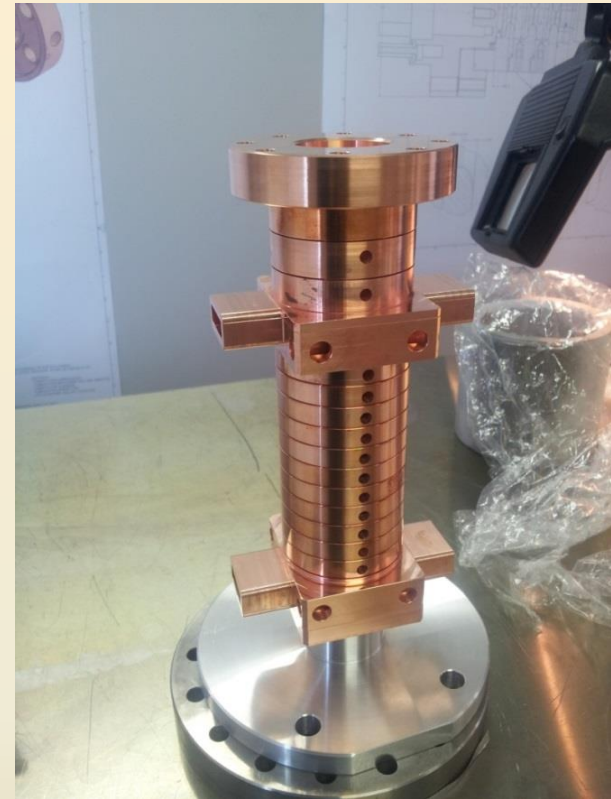
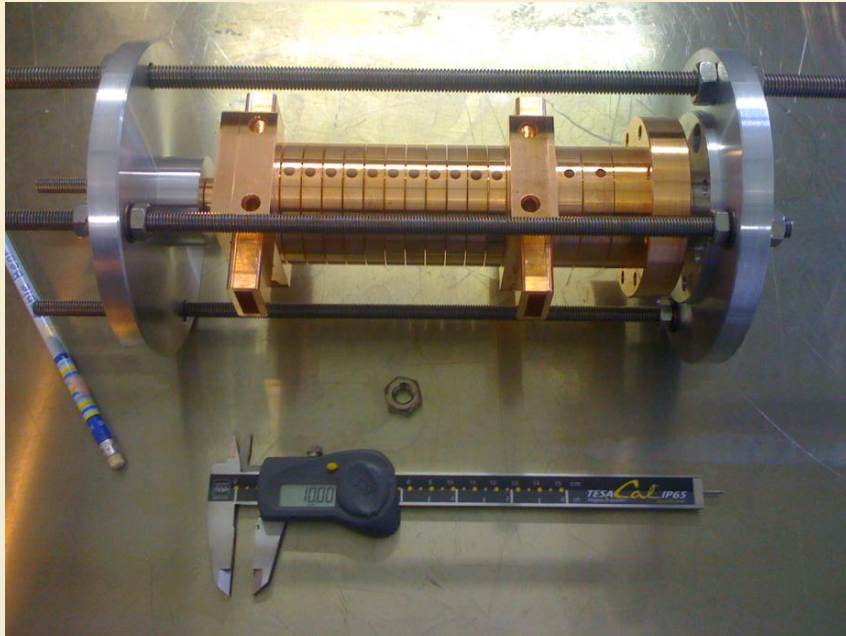
11.424 GHz

▪It is necessary to evaluate a different design for an appropriate configuration of magnets

▪We limited the electric field to 200MV/m and so to reach 3.5MeV (energy level needed for the applications that we are investigating) the SW section must be expanded to 2.6 cells.

**New materials or multilayers are needed in order to get 240 MV/m !!**

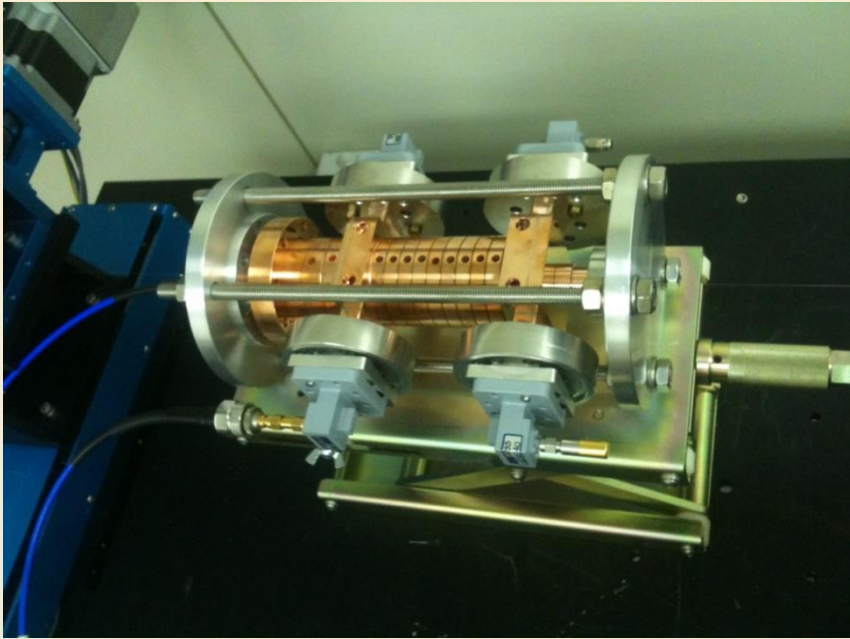
# 11.424 GHz Hybrid gun fabricated at INFN-LNF



**The hybrid gun has been designed at UCLA  
[J. Rosenzweig and Ph.D. thesis of A. Valloni ]**



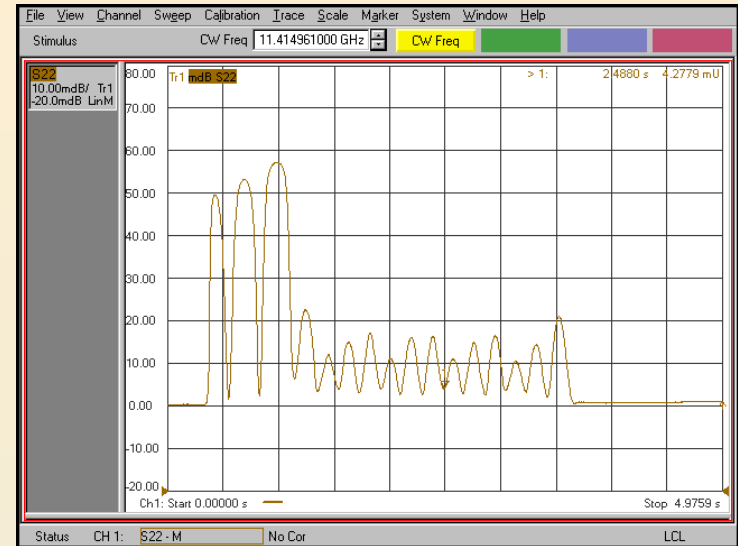
# 11.424 GHz hybrid gun prototype under test (with the untuned device and no brazing).



Machining precision is  $\pm 2.5 \mu\text{m}$  while roughness is  $\sim 60 \text{ nm}$ .

The surface finishing was obtained directly by mechanical machining with custom cutting tools (diamond mono-crystal)

11.424 GHz hybrid photoinjector longitudinal electric field profile (with the untuned device and no brazing). **Mode frequency is  $\sim 7 \text{ MHz}$  off**



11.424 GHz hybrid photoinjector longitudinal phase advance (with the untuned device, no tuners and no brazing). **Mode frequency is  $\sim 7 \text{ MHz}$  off**



# Future activities

Higher power tests at SLAC **on the electroformed structure**

R&D to increase the conductivity **of Au films**

**We will continue developing technologies** suitable for practical structures of new shapes and with new materials (e.g., multilayers)

**Brazing** and **higher power tests** on the 11.424 GHz hybrid gun and additional studies with a **multilayers film** in order to increase the peak field in the SW region (**up to 240 MV/m !!**)